

SEP 24 2004

Atty Dkt. No.
33082M119**PATENT****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of: Hitoshi Kato, et al.

Serial No.: 10/066,627

Group Art Unit: 2812

Filed: February 6, 2002

Examiner: Unassigned

For: SILICON NITRIDE FILM FORMING METHOD, SILICON NITRIDE FILM
FORMING SYSTEM AND SILICON NITRIDE FILM FORMING SYSTEM
PRECLEANING METHOD**INFORMATION DISCLOSURE STATEMENT**Commissioner for Patents
Washington, D.C. 20231

Sir:

Pursuant to the duty of disclosure under 37 C.F.R. 1.56, Applicants are enclosing an
Information Disclosure Citation Form (PTO-1449) and a copy of the cited document.

It is respectfully requested that the cited document be considered by the Examiner in the
above-identified patent application and that the cited document be made officially of record
therein. It is further requested that a listing of the same appear on the face of any patent which
may issue from this application.

Respectfully submitted,

SMITH, GAMBRELL & RUSSELL, LLP



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PATENT TRADEMARK OFFICE

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Dated: March 19, 2002

FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT	ATTY. DOCKET	SERIAL NO.
	33082M119	10/066,627
	Hitoshi Kato, et al..	
	FILING DATE	GROUP ART UNIT
	February 6, 2002	2812

U.S. PATENT DOCUMENTS

*Examiner's Initials		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE, IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

FOREIGN PATENT DOCUMENTS

*Examiner's Initials		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES NO	
	AH	10-125666	5/15/98	Japan			Abstract	
	AI							
	AJ							
	AK							
	AL							

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

	AM	
	AN	
	AO	
	AP	
	AQ	
	AR	
EXAMINER:		DATE CONSIDERED:
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>		